

METHOD FOR SHRINKING THE IMAGE OF PHOTORESIST

ABSTRACT OF THE INVENTION

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First of all, a semiconductor substrate with a photoresist layer thereon is provided. Then a photoresist region is formed on the semiconductor substrate by a photolithography process. Next, a chemical reaction layer is formed within the photoresist region. Subsequently, a 10 developing process is performed to remove the chemical reaction layer within the photoresist region to shrink the photoresist region in line width on the semiconductor substrate.